

Layout Pattern-driven Design Rule Evaluation

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Introduction

- Restrictive patterning technologies (e.g. LELE, SADP, LELELE) → non-manufacturable patterns
 - Each restrictive technology will affect routability of standard cells/design
 - Which technology to adopt?
- Sub-wavelength photolithography → Bad Patterns



Candidate Solutions to "Bad Patterns" Problem

- <u>Design Phase</u>: Prohibit ALL candidate bad patterns
 - <u>Why not?</u> Standard Cell Routability becomes HARDER→ BIGGER area
- Hybrid Approach:
 - Only prohibit <u>selected</u> "forbidden patterns" at Design Phase
 - Fix the rest **post-Route**, in a **best effort** manner
 - Sometimes process needs to try to allow those patterns with penalty
- Post-Route Phase: Allow all candidate bad patterns in design, fix them later [e.g. Legalization]
 - E.g. Flow which uses router and a pattern checker and fixer (Yang et al; SPIE 2010)
 - <u>Why not?</u> May be too late

Forbidden Patterns

- What is a good choice of patterns to **forbid**?
 - Highest yield-impact
 - Usually identified by lithography simulation and from failing chips data
 - Low routability-impact
 - Patterns that if forbidden:
 - don't harshly penalize routability

➔ Need an evaluation method early in the process to assess the impact of prohibiting bad patterns, as part of design rules evaluation



Forbidden Patterns



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Pattern-DRE

- Performs Pattern-aware Design Rule Evaluation
- Quick assessment of sensitivity of routability to some bad patterns > select forbidden patterns
- Built on top of DRE (TCAD'12, ASPDAC'14)





Agenda

- Overview of Design Rule Evaluation Framework (DRE)
- Flow of Pattern-DRE framework
- Validation
- Sample Studies using Pattern-DRE



DRE

- A framework for early exploration of design rules, layout methodologies, and library architectures
- Standard cell-level evaluation and chip-level evaluation
- Not Pattern-aware



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FLOW OF PATTERN-DRE

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Flow of Pattern-DRE



Flow of Pattern-DRE



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Routing Options Generator

- For each net, enumerate possible wiring solutions in the net's bounding box
 - Use Single Trunk Steiner Tree topology

6 Wiring solutions for this net



Routing Options Generator (cont'd)

- Enumeration of combinations of wiring solutions of all nets→ candidate routing options
 - Tree traversal
- Tree branches pruned as soon as **conflict** is found
- Conflict example:
 - Contact for Net#1

Contact for Net#2



Routing Solution #1: CONFLICT→ rejected



Routing Solution #2: **VALID**

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Tile/Pattern Representation

- Layout is represented as 2D matrix of tiles.
- Each tile/pattern is represented by
 - a segment representation [unique]
 - a node representation [necessary for conflict check]
- For a 2x2 tile:

```
Segment representation
```



=> 100011010000 => 2256

Node representation



 Both representations are serialized as binary strings and saved as a number

Conflict Detection

- A conflict occurs between wiring solutions of 2 nets if in any tile :
 - Wires overlap
 - Detected by bitwise ANDing of segments for each tile:



- OR Wires cross
 - Detection by bitwise ANDing of nodes in the same tile







CONFLICT!

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- 4 Nets:
 - A1 & A2:
 - 2 inputs
 - Each is a single contact net
 - ZN: output
 - Net_000







First wiring solution for **net_000**

Another wiring solution for **net_000**

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First wiring solution for **zn**

Another wiring solution for **zn**

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• Two of the several complete routing options



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Flow of Pattern-DRE



2. Forbidden Patterns Checker

- Input:
 - list of forbidden patterns
 - Can be any size till 5 tracks x 5 tracks (currently)
 - All valid routing options
- Each generated routing option is checked against all forbidden patterns
 - Slide a window and check every formed pattern
 - − If a match occurs → discard routing option
- Very fast because of pattern representation





Flow of Pattern-DRE



Routability Metrics

- Two Metrics reported:
 - 1. Number of routable cells
 - Cells which have non-zero number of routing options
 - 2. Total number of routing options
- Also reports number of occurrences of all patterns



How to Compare 2 Sets of Forbidden Patterns?

- Given Set A, Set B of forbidden patterns
- Run Pattern-DRE twice
 - 1. Set A is set of forbidden patterns
 - 2. Set B is set of forbidden patterns
- If Set A has less routable cells → Set A has higher routability impact
- If same number of routable cells → check the total number of routing options
 - Assume Set A has smaller number
 - harder to route the cells without patterns of Set A
 - →Less chance of successful **post-route fix** for rest of patterns
 - → Set A has higher routability impact



Flow of Pattern-DRE



Minimum Number of Unroutable Nets

- The routing options generator may fail to find a conflict-free routing option for the cell.
- Objective: find the routing solution with minimum number of unrouted nets
- Formulated and solved as ILP.



VALIDATION, EXPERIMENTS & RESULTS

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Validation

Device-layer generation:

- Less than 2% average error in area in comparison to Nangate
 Open Cell Library
- 38 minutes for entire library on single CPU

Routing estimation

 12% higher wire-length on average and 44x faster in comparison to FLUTE Steiner-tree router (C.Chu et al; TCAD 2008)

Pattern Counting

- Patterns that contribute to ~82.4% in Nangate layouts, take up ~81.5% of counts in our approach
- Cosine Similarity = 0.86
 - Measured for 2 vectors of pattern counts Nangate vs. PatternDRE



Metrics Index

- <u>Routing Options</u>: Total number of valid nonforbidden routing options of all cells
- <u>Routable cells</u>: Number of cells that have nonzero number of routing options



Experiment #1: SADP vs. LELE

- <u>Objective</u>: how much routability do we sacrifice for better overlay control?
- For SADP: assume trim not allowed to create any edges (no overlay sensitive edges)
 - Most of the patterns that are SADP-compliant are LELE-compliant
 - Some patterns are considered LELE-compliant but not SADPcompliant



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Experiment #1: SADP vs. LELE (cont'd)

• Samples of forbidden patterns (258 patterns)



 Disclaimer: for proper conclusions, enumerate all SADP –incompatible patterns that are allowed by LELE



Experiment #1: SADP vs. LELE (cont'd)

- **SADP**: with forbidden patterns
- **LELE**: without any forbidden patterns

	Routable Cells	Routing Options	Change in Routing Options
SADP	77	2766	-17%
LELE	78	3338	

Sacrifice 1 routable cell and 17% of routing options for better overlay control



Experiment #2: LELE vs. EUVL

- Forbidden patterns:
 - LELE:
 - Patterns of size 4x4
 - Enumerated then found LELE-incompliant using commercial DP decomposer
 - EUVL: none

	Routable Cells	Routing Options	Decrease in Routing Options
LELE	72	1440	56.9%
EUVL	78	3338	

 By using LELE instead of the unconstrained EUVL, we sacrifice routability of 7.8% of the cells, and 56.9% of the routing options.

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Experiment #3: Diffusion Location

- **Objective:** compare two front-end choices for location of diffusion area:
 - Close to power rails
 - Close to P/N interface

Diffusion Location	Routable Cells	Routing Options	Decrease in Routing Options
Close to Power rail	78	2772	
Close to P/N interface	74	861	6.9%



Conclusion

- Proposed Pattern-aware Design Rule Evaluation framework
- Can be used to assess the implications of certain restrictive technologies, or blocking bad patterns

Future Work

 Integrate with a lithography simulator to consider yield-severity of patterns



QUESTIONS?





Backup

Device-layers Generator



ICCAD'11, TCAD'12





1. Routing Options Generator (cont'd)

- If bounding box of the net has skewed aspect ratio → long wiring in one direction
 - Ignore routing solutions with trunk in that direction



